

FORM PTO-1449

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

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|------------------------|-------------------|
| Attorney Docket Number | 42637/GDL/N288 |
| Application Number | To be assigned |
| Filing Date | December 17, 2001 |
| Applicant(s) | Jayant Neogi |
| Group Art Unit | To be determined |
| Examiner Name | To be determined |

FOREIGN PATENT DOCUMENTS

| EXAMINER INITIALS | DOCUMENT NUMBER | PUBLICATION DATE | COUNTRY OR PATENT OFFICE | CLASS | SUBCLASS | TRANSLATION | |
|-------------------|-----------------|------------------|--------------------------|-------|----------|-------------|----|
| | | | | | | YES | NO |
| <i>JN</i> | WO 99/34197 | 07/1999 | WIPO | | | | |
| <i>JN</i> | 2033096A | 05/1980 | GB | G03B | 41/00 | | |

OTHER DOCUMENTS

| | | | |
|--------------------|--|-----------------|----------|
| EXAMINER INITIALS | Include name of the author (in CAPITAL LETTERS), title of the article, title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | | |
| <i>JN</i> | BRAUNSTEIN, et al., Depth profile of antimony implanted into diamond, Journal of Applied Physics, Vol. 50, No. 9, September 1979, Pgs. 5731 - 5735. | | |
| <i>JN</i> | ENDENFELD et al., Force probe characterization using silicon three-dimensional structures formed by focused ion beam lithography, Journal of Vacuum Science and Technology B, Vol. 12, No. 6, 1994, Pgs. 3571-3575. | | |
| <i>JN</i> | KOMURO, Ion Beam Exposure Apparatus Using Liquid Metal Source, 1982, Pgs. 155-159, Elsevier Squoia; Netherlands | | |
| <i>JN</i> | International Search Report for PCT/US00/16761 Dated October 2, 2000 | | |
| EXAMINER SIGNATURE | <i>JN</i> | DATE CONSIDERED | 06/13/03 |

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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